

<b>FORM PTO-1449</b>  <b>INFORMATION DISCLOSURE STATEMENT</b>				<b>Atty Docket</b>  <b>TAI 145</b>		<b>Application No.</b>  <b>To Be Assigned</b>	
				<b>Applicant</b>  <b>Toyokazu Sakata</b>			
				<b>Filing Date</b>  <b>November 26, 2003</b>		<b>Group Unit</b>  <b>To Be Assigned</b>	
<b>U.S. PATENT DOCUMENTS</b>							
Examiner Initial		Document Number	Date	Name	Class	Sub- Class	Filing Date
LV	AA	6,355,572	03/12/02	Ikegami			
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
<b>FOREIGN PATENT DOCUMENTS</b>							
		Document Number	Date	Country	Class	Sub- Class	Trans- lation
LV	AK	7-94483	04/07/95	Japan			Abstract
LV	AL	2001-77086	03/23/01	Japan			Abstract
	AM						
	AN						
<b>OTHER (Including Author, Title, Date, Pertinent Pages, etc.)</b>							
LV	AO	"Dry Etching of Organic Low Dielectric Constant Film without Etch Stop Layer" M.Mizumura et al. JJAP, Vol. 41, pp. 425-427 (no date)					
LV	AP	"Highly Selective Etching of Organic SOG to SiN for Cu Damascene Interconnects Using New Gas Chemistry of C <sub>4</sub> F <sub>8</sub> /N <sub>2</sub> /Ar" S. Uno et al. Proc. Of Dry Process Symp., pp. 215-220(1999)					
	AQ						
<b>Examiner</b> LAN VINH				<b>Date Considered</b> 7/18/05			
<b>EXAMINER:</b> Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.							